

an Open Access Journal by MDPI

Correlative Microscopy: Workflows and Applications in Materials Science

Guest Editors:

Dr. Francesco Mura

Department of Basic and Applied Sciences, Sapienza University of Rome, Via A. Scarpa 16, 00161 Rome, Italy

Prof. Dr. Marco Rossi

Department of Basic and Applied Sciences for Engineering, Sapienza University of Rome, Via A. Scarpa 16, 00161 Rome, Italy

Dr. Daniele Passeri

Department of Basic and Applied Sciences for Engineering, Sapienza University of Rome, Via A. Scarpa 14, 00161 Rome, Italy

Deadline for manuscript submissions: **30 September 2024**

mdpi.com/si/199538

Message from the Guest Editors

Almost 40 years have passed since the first paper was published by M. Osborn, R.E. Webster and K. Weber describing the possibility of combining light and electron microscopy to observe the same region of interest. Later, this particular approach to microscopy became known as correlative microscopy, and the combination of these two techniques is called CLEM—Correlative Light to Electron Microscopy. For a long time, this technique was strictly limited to the life sciences, but the need for specific and different information from a particular region of interest has extended this approach to materials science, including other characterization techniques such as RAMAN, AFM or XRM.

In this Special Issue, original research articles and reviews are welcome. Research areas may include (but are not limited to) the following:

Application of different combinations of correlative microscopy in material science.

Development of innovative workflows for fast and accurate correlative microscopy.

Methods of data analysis for correlative microscopy, including the employment of IA systems.

